

1. A method for making an organic transistor on a substrate comprising the steps of:

providing a substrate including a metal surface layer;

providing a rotatable stamp having relief geometries on its surface to define a stamping surface;

applying a SAMS ink to the surface of the rotatable stamp to define an inked stamping surface;

rotating the rotatable stamp on the metal surface layer as the layer is placed in contact with the stamp to form on the layer a self-assembled monolayer pattern as defined by the inked stamping surface; and

patterning the layer by etching material from the layer wherein the inked stamping surface guides the etching in a geometry to define the patterned layer useful in fabricating an electronic device;

removing the inked pattern from the layer; and

applying an organic semiconductor layer overlying the etched metal layer.